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u+ electrically grounded surface on one side thereof, the surface being exposed to plasma in the plasma reaction chamber during use of the electrode.

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B2 3. (Amended) The electrode of Claim 1, wherein the gas outlets have diameters of 0.020 to 0.030 inch and the gas outlets are distributed across the exposed surface.

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B3 10. (Amended) A plasma reaction chamber including the showerhead electrode of Claim 1, the showerhead electrode being bonded or clamped to a temperature-controlled member in an interior of the plasma reaction chamber, the temperature-controlled member including a gas passage supplying a process gas to the showerhead electrode, the temperature-controlled member including a cavity and at least one baffle plate located in the cavity, the gas passage supplying process gas so as to pass through the baffle prior to passing through the showerhead electrode.

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B4 23. (Amended) The electrode of Claim 21, wherein the backing plate includes gas distribution holes communicating with the gas outlets in the electrode.

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B5- 27. (Amended) The electrode of Claim 1, wherein the gas outlets comprise ultrasonically drilled holes.

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B6 30. (Amended) The electrode of Claim 1, having a thickness of about 0.375 to 0.5 inch.

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